

**REMARKS**

Applicants hereby elect with traverse the prosecution of Group I, device claims 1-10. Non-elected claims 11-20 have been withdrawn from further consideration by the Examiner. The restriction requirement is further respectfully traversed for the following reasons. While the Examiner contended in the 01/13/2005 Office Action, "the device of Group I invention could be made by a process different from those of the Group II invention. For example, rather than using an implantation step for the wells instead of doping". The Applicants respectfully submit that an implantation step is a chemical process that is used for doping a semiconductor material and therefore, an implantation step is the same as a doping step. As such, the Group I device invention can only be made by the process contained in the Group II method invention.

The restriction requirement is therefore respectfully traversed. The examination of Group I, claims 1-10, together with the examination of Group II claims 11-20, is respectfully requested of the Examiner.

Respectfully submitted,

A handwritten signature in black ink, appearing to read 'Randy W. Tung', is written over a horizontal line.

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